

AVAILABLE FOR PRE-ORDER

SCIVAX

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RubiQ™

TYPE RD-100

Compact and easy to use nanoimprint lithography (NIL) tool for R&D and pilot scale patterning. The modular design incorporates the processing capabilities and benefits of the SCIVAX foundry service technology.



Types and Function



Description

Thermal or UV

- Thermoplastic resin for Thermal NIL.
- UV curable resin for UV NIL.

Higher Pressure

- Unique high pressure feature enables high aspect ratio structures and improve thickness control.

Parallel Plate

- Parallel plate mode is ideal for hard masters such as silicon.

FLAN (Air assisted press)

- Useful with soft or flexible working stamps to give better conformability, pattern curved surfaces, and tolerance to particles.

SKU : 14 types available (7x2)

CURE → ↓ PRESS	Thermal	UV	Both
Parallel Plate	✓	✓	N/A
FLAN (Air assisted)	✓	✓	✓
Both	✓	✓	N/A

Maximum pressure

Low (10kN) Air cylinder

High (20kN) Servo motor

✓ : Available



TYPE RD-100

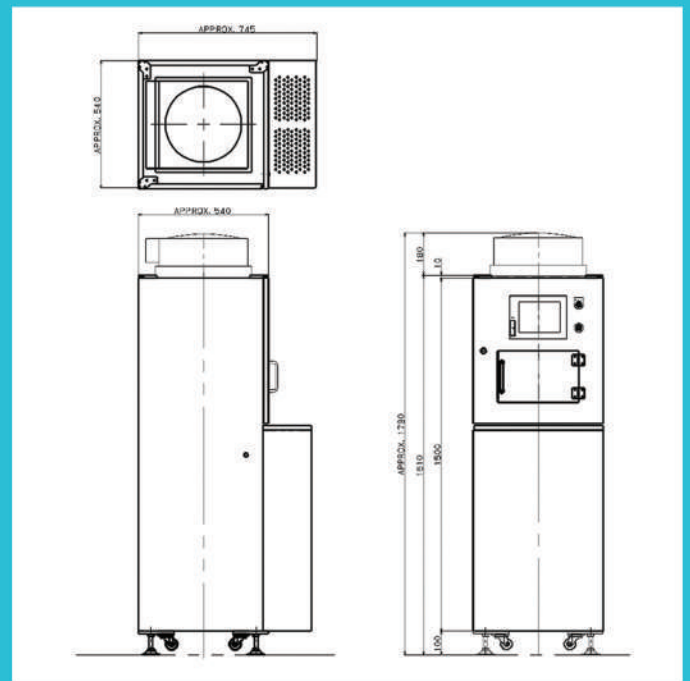
Next Generation NIL Tool



Key Features

- Design from experience of over 1,000 prototypes
- R&D to Small Pilot Scale
- Modular Design (industry first)
- Extensibility
- Up to 14 types of combination meets your purpose and budget
- Excellent Uniformity over entire substrate
- Work size $\sim \phi 100\text{mm}$

Schematic Drawing



Dimension: W500*D700*H1700(mm)
Weight: 260kg~



Contact us for detailed specification and utility!



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